ABSTRACT OF THE DISCLOSURE

An exposure method is provided so that the divided regions of defined on a wafer are successively exposed using pulses of laser light emitted from an excimer laser light source in such a way that each region receives a different level of target exposure levels. And, transmittance of a coarse energy adjuster, having a number of neutral density filters, is adjusted so that a sub-divided region receiving the least number of exposure pulses can receive a pulse count that exceeds the minimum number of exposure pulses required for optimal exposure. During the process of scanning exposure, transmittance of the coarse energy adjuster is held constant so that, to compensate for variations in the pulse energy, the output power of the excimer laser light source is adjusted according to real-time data output from an integrator sensor.